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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of
Toshikazu SEGAWA et al

531 Rec'd PC

25 OCT 2001

S. N.

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For: METHOD OF PRODUCING PHASE MASK FOR PROCESSING OPTICAL FIBER AND
OPTICAL FIBER WITH BRAGG DIFFRACTION GRATING FABRICATED BY USING
THE OPTICAL FIBER-PROCESSING PHASE MASK

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Please make the following amendments to this application
prior to examination thereof:

In the Specification:

Page 10, lines 9-11, please replace this paragraph with the
following:

Figs. 2(a) and 2(b) comprise diagrams showing an electron
beam writing method used in the method of producing a phase mask,
and also showing a section of the phase mask.

Page 10, lines 15-19, please replace these paragraphs with
the following:

Figs. 4(a) through 4(h) are sectional views showing steps of
an embodiment of the phase mask producing method according to the
present invention.

Figs. 5(a) through 5(c) comprise diagrams for describing
optical fiber processing and a phase mask used therefor.

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